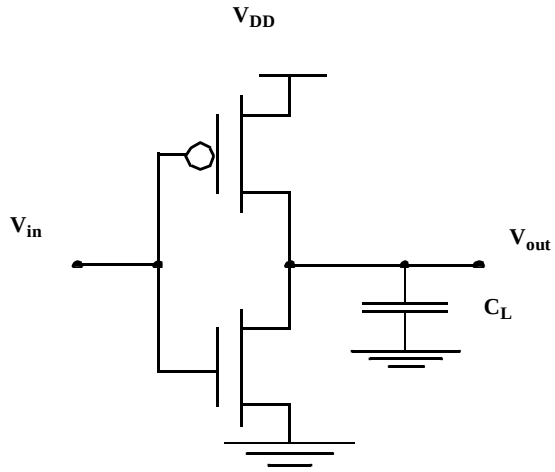
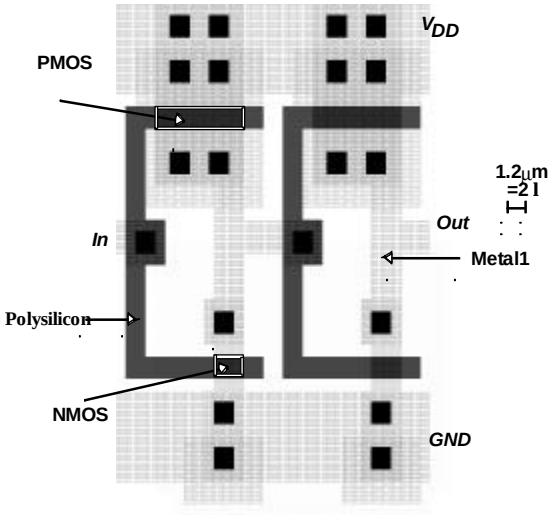
CMOS INVERTER

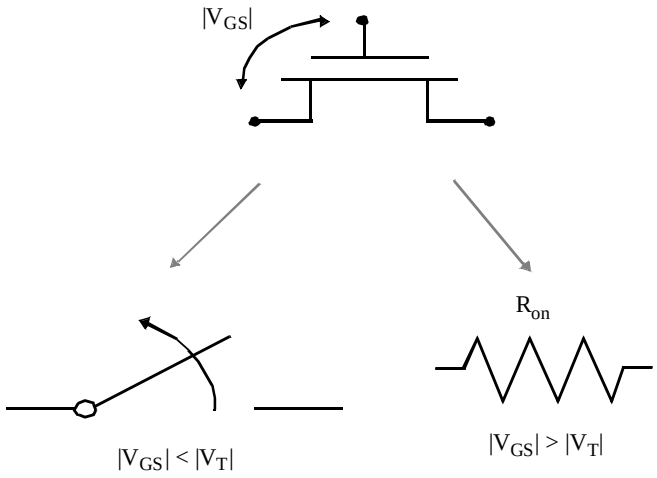
The CMOS Inverter: A First Glance



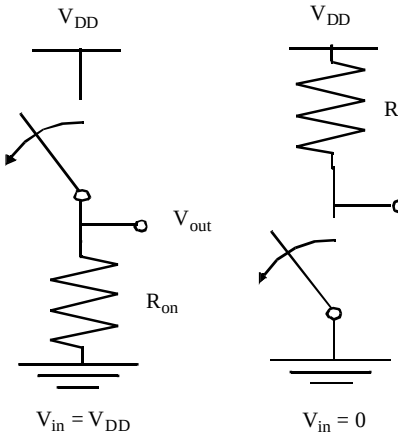
CMOS Inverters



Switch Model of CMOS Transistor



CMOS Inverter: Steady State Response

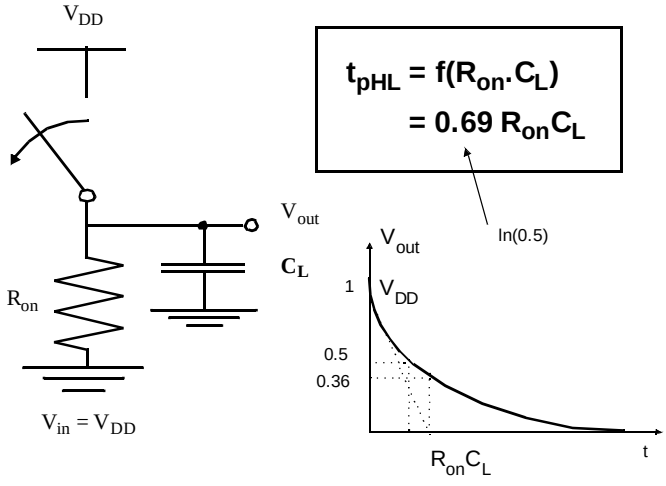


$V_{OH} = V_{DD}$

$V_{OL} = 0$

$V_M = f(R_{onn}, R_{onp})$

CMOS Inverter: Transient Response



$t_{pHL} = f(R_{on}.C_L)$

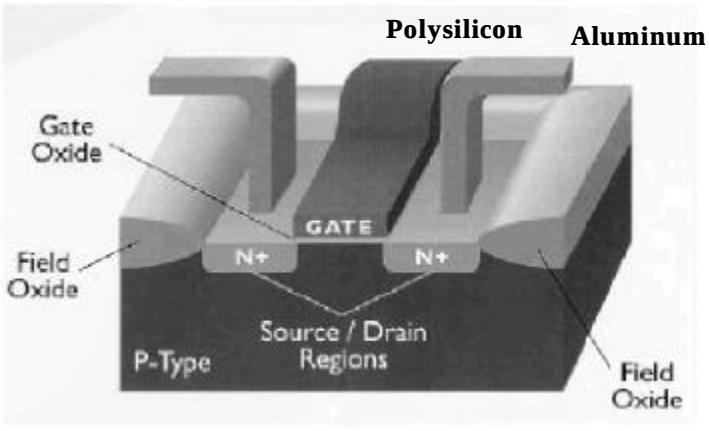
$= 0.69\ R_{on}C_L$

ln(0.5)

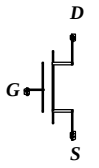
CMOS Properties

- Full rail-to-rail swing
- Symmetrical VTC
- Propagation delay function of load capacitance and resistance of transistors
- No static power dissipation
- Direct path current during switching

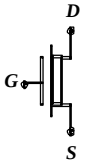
The MOS Transistor



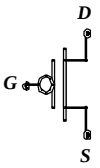
MOS Transistors - Types and Symbols



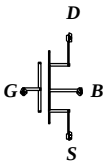
NMOS Enhancement



NMOS Depletion

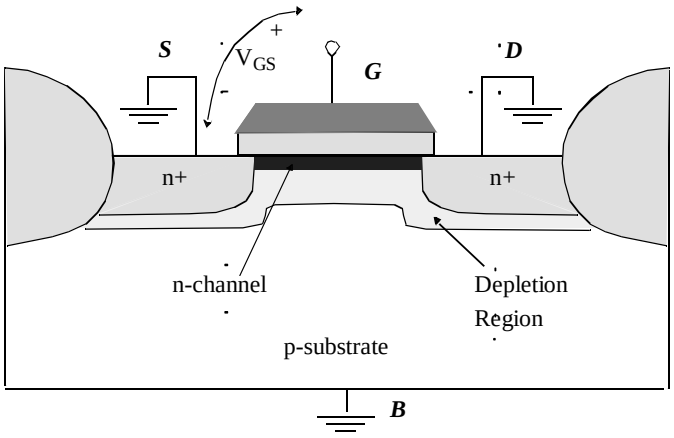


PMOS Enhancement



NMOS with Bulk Contact

Threshold Voltage: Concept



The Threshold Voltage

$$V_T = \phi_{ms} - 2\phi_F - \frac{Q_B}{C_{ox}} - \frac{Q_{SS}}{C_{ox}} - \frac{Q_I}{C_{ox}}$$

Workfunction Difference

Depletion Layer Charge

Surface Charge

Implants

Body Effect Coefficient

$$V_T = V_{T0} + \gamma\left(\sqrt{\left|-2\phi_F + V_{SB}\right|} - \sqrt{\left|-2\phi_F\right|}\right)$$

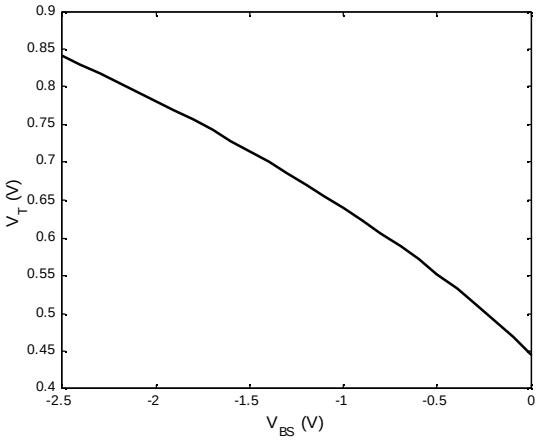
with

$$V_{T0} = \phi_{ms} - 2\phi_F - \frac{Q_{B0}}{C_{ox}} - \frac{Q_{SS}}{C_{ox}} - \frac{Q_I}{C_{ox}}$$

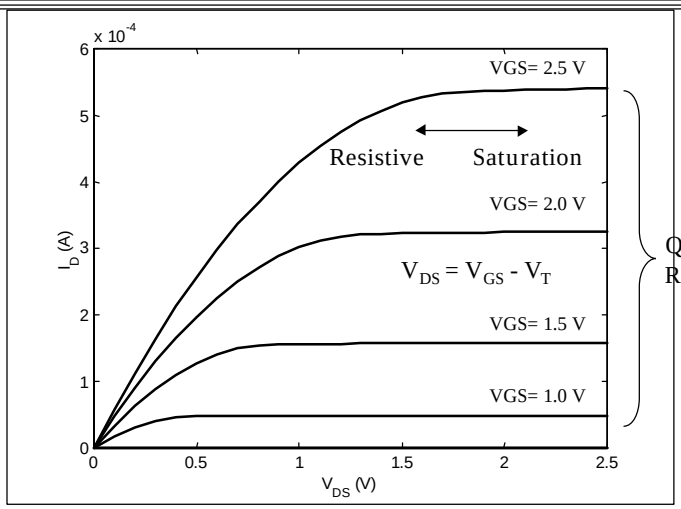
and

$$\gamma = \frac{\sqrt{2q\varepsilon_{si}N_A}}{C_{ox}}$$

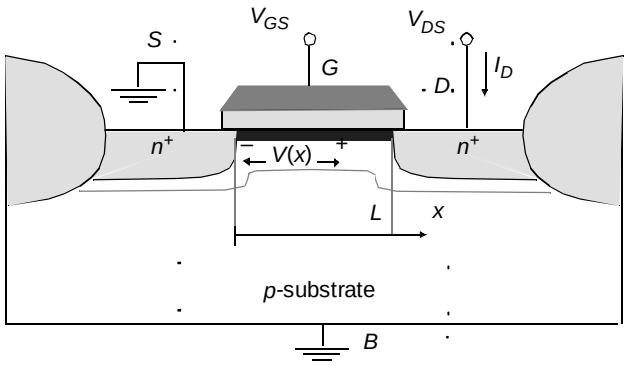
The Body Effect



Current-Voltage Relations
A good ol'transistor

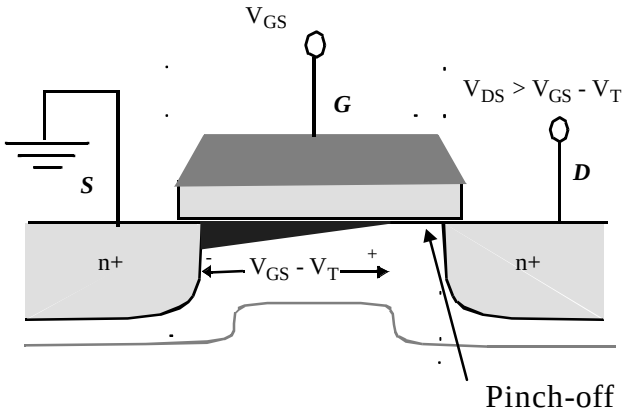


Transistor in Linear



MOS transistor and its bias conditions

Transistor in Saturation



Current-Voltage Relations Long-Channel Device

Linear Region: $V_{DS} \leq V_{GS} - V_T$

$$I_D = k'_n \frac{W}{L}\left((V_{GS} - V_T)V_{DS} - \frac{V_{DS}^2}{2}\right)$$

with

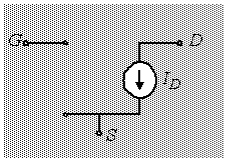
$$k'_n = \mu_n C_{ox} = \frac{\mu_n \varepsilon_{ox}}{t_{ox}}$$ Process Transconductance Parameter

Saturation Mode: $V_{DS} \geq V_{GS} - V_T$

Channel Length Modulation

$$I_D = \frac{k'_n}{2}\frac{W}{L}(V_{GS} - V_T)^2(1 + \lambda V_{DS})$$

A model for manual analysis



$$V_{DS} > V_{GS} - V_T$$

$$I_D = \frac{k'_n}{2}\frac{W}{L}(V_{GS} - V_T)^2(1 + \lambda V_{DS})$$

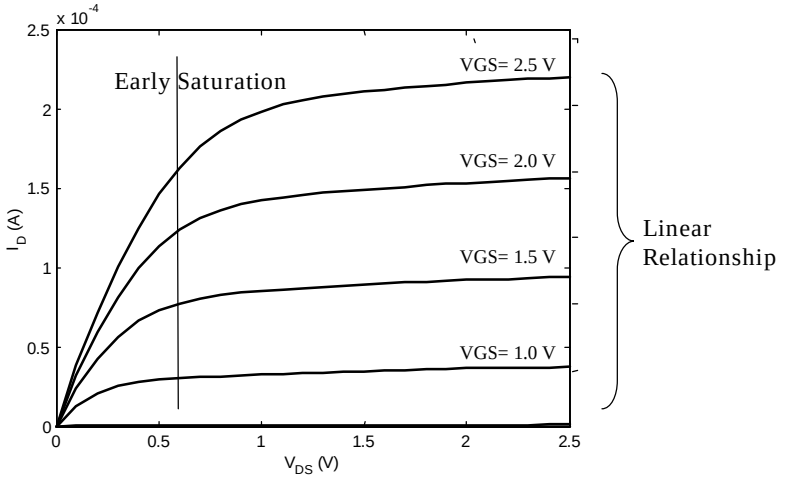
$$V_{DS} < V_{GS} - V_T$$

$$I_D = k'_n \frac{W}{L}\left((V_{GS} - V_T)V_{DS} - \frac{V_{DS}^2}{2}\right)$$

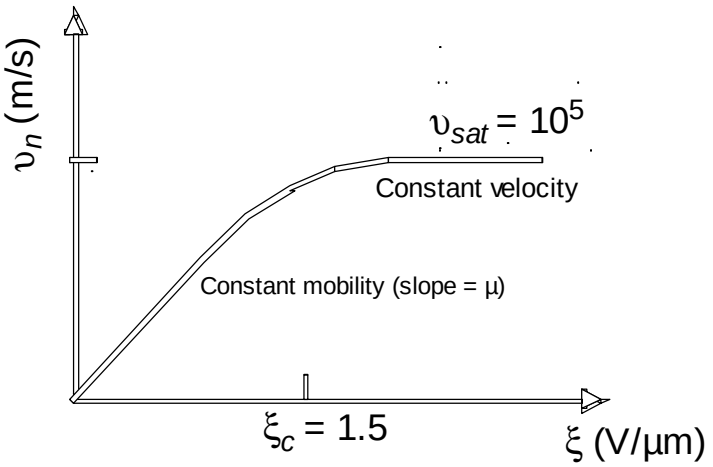
with

$$V_T = V_{T0} + \gamma\left(\sqrt{\left|-2\phi_F + V_{SB}\right|} - \sqrt{\left|-2\phi_F\right|}\right)$$

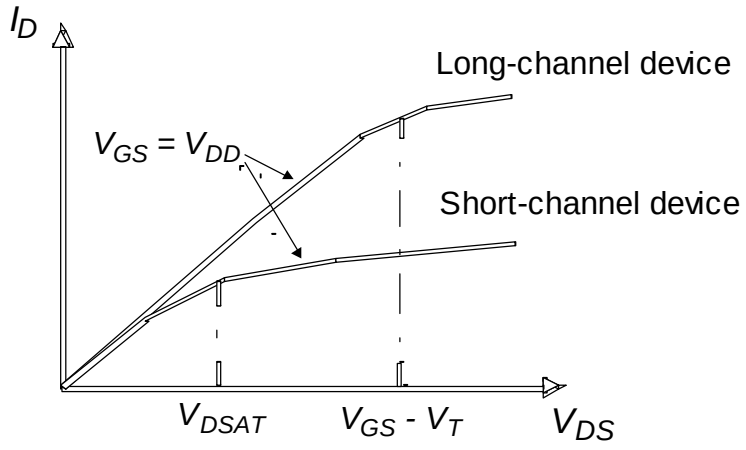
Current-Voltage Relations The Deep-Submicron Era



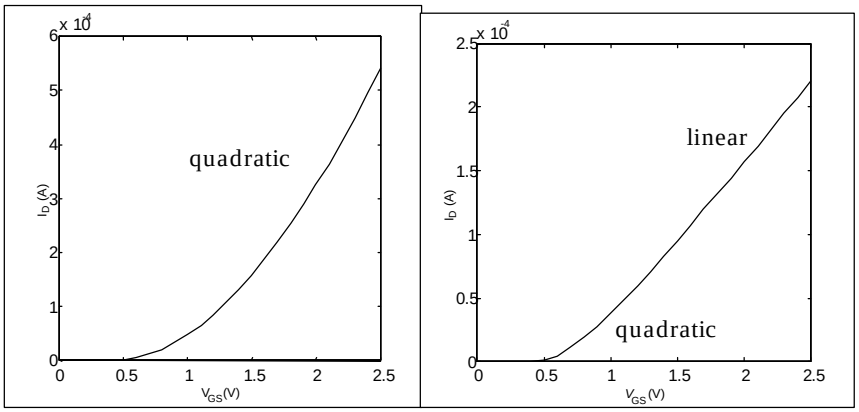
Velocity Saturation



Perspective



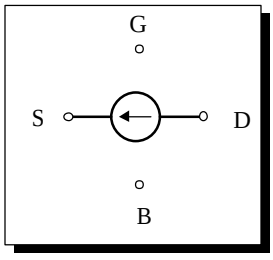
I_D versus V_{GS}



Long Channel

Short Channel

A model for manual analysis



$$I_D = 0 \text{ for } V_{GT} \le 0$$

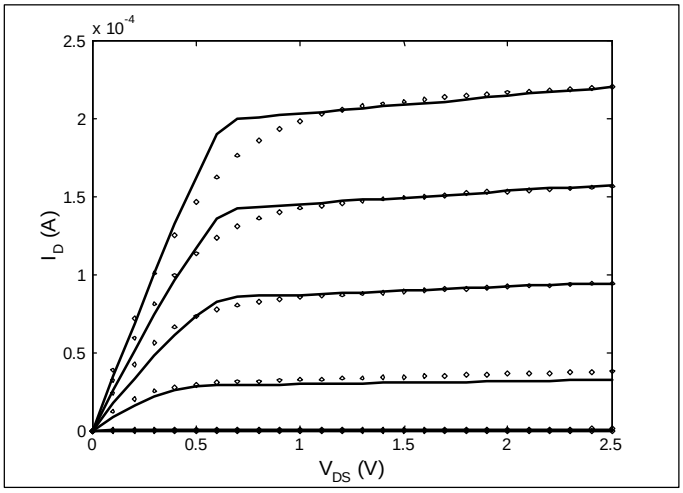
$$I_D = k' \frac{W}{L}\left(V_{GT}V_{min} - \frac{V_{min}^2}{2}\right)(1 + \lambda V_{DS}) \text{ for } V_{GT} \ge 0$$

with $V_{min} = \min(V_{GT}, V_{DS}, V_{DSAT})$,

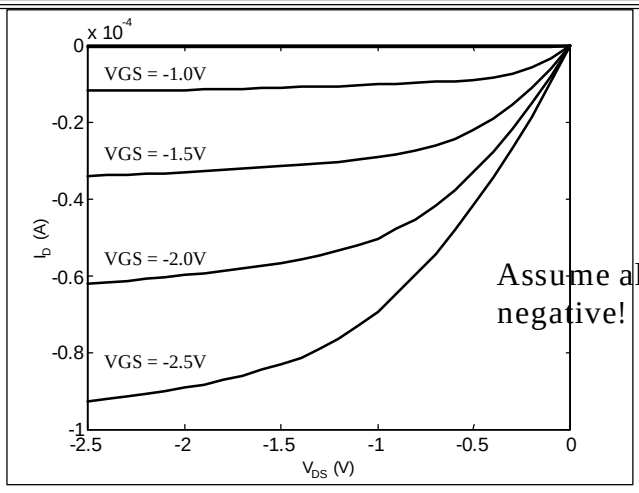
$V_{GT} = V_{GS} - V_T$,

and $V_T = V_{T0} + \gamma(\sqrt{|-2\phi_F + V_{SB}|} - \sqrt{|-2\phi_F|})$

Simple Model versus SPICE



A PMOS Transistor



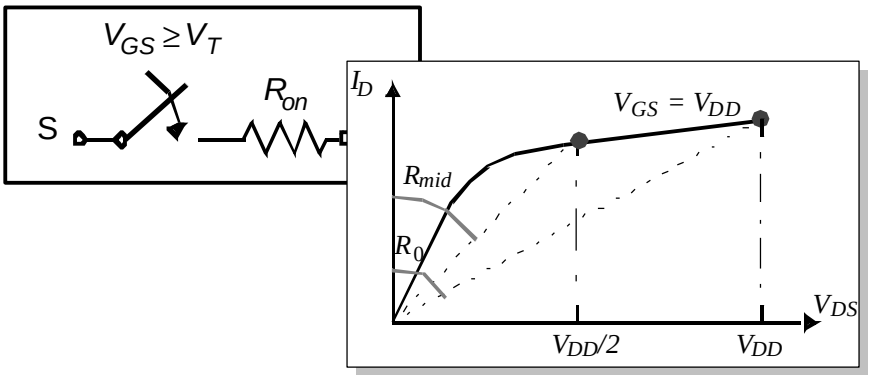
Assume all variables negative!

Transistor Model for Manual Analysis

Table 3.2 Parameters for manual model of generic 0.25 μm CMOS process (minimum length device).

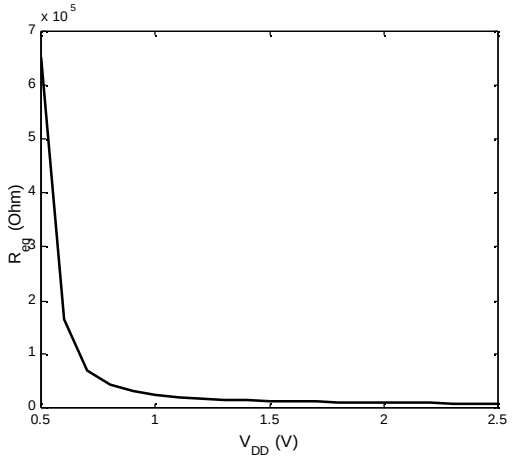
	V_{T0} (V)	γ ($V^{0.5}$)	V_{DSAT} (V)	K' (A/V^2)	λ (V^{-1})
NMOS	0.43	0.4	0.63	115×10^{-6}	0.06
PMOS	−0.4	-0.4	-1	-30×10^{-6}	-0.1

The Transistor as a Switch



$$R_{eq} = \frac{1}{2}\left(\frac{V_{DD}}{I_{DSAT}(1+\lambda V_{DD})} + \frac{V_{DD}/2}{I_{DSAT}(1+\lambda V_{DD}/2)}\right) \approx \frac{3}{4}\frac{V_{DD}}{I_{DSAT}}\left(1-\frac{5}{6}\lambda V_{DD}\right)$$

The Transistor as a Switch



The Transistor as a Switch

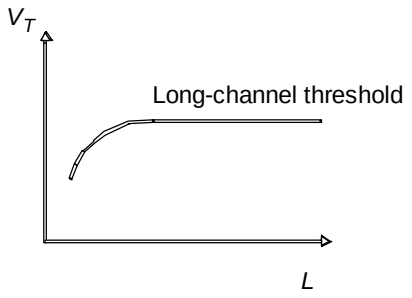
Table 3.3 Equivalent resistance R_{eq} (W/L= 1) of NMOS and PMOS transistors in 0.25 μm CMOS process (with $L = L_{min}$). For larger devices, divide R_{eq} by W/L.

V_{DD} (V)	1	1.5	2	2.5
NMOS (kΩ)	35	19	15	13
PMOS (kΩ)	115	55	38	31

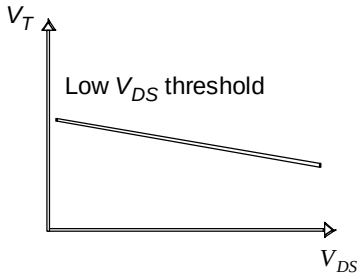
The Sub-Micron MOS Transistor

- **Threshold Variations**
- **Subthreshold Conduction**
- **Parasitic Resistances**
- **Latch-up**

Threshold Variations

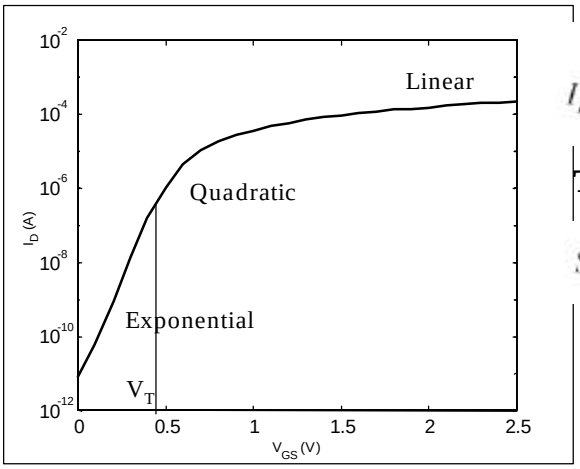


Threshold as a function of the length (for low V_{DS})



Drain-induced barrier lowering (for low L)

Sub-Threshold Conduction



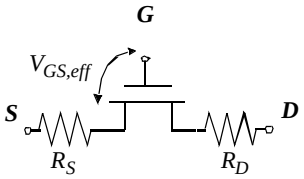
$$I_D = I_S e^{\frac{V_{GS}}{nkT/q}}\left(1 - e^{-\frac{V_{DS}}{kT/q}}\right)$$

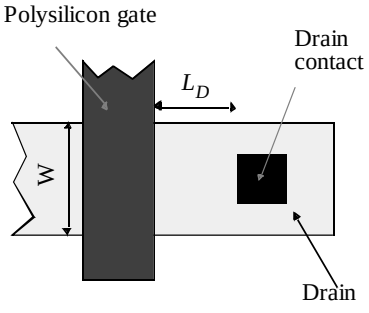
The Slope Factor

$$S = n\left(\frac{kT}{q}\right)\ln(10)$$

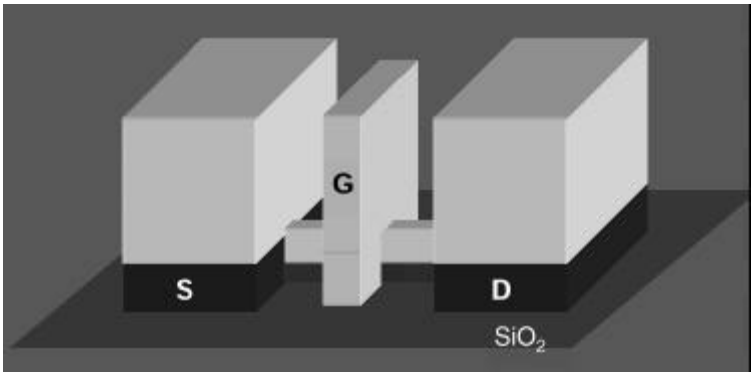
Typical values for S:
60 .. 100 mV / decade

Parasitic Resistances





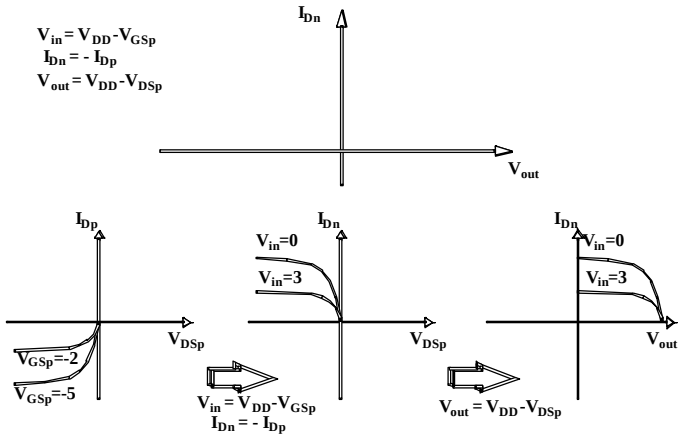
Future Perspectives



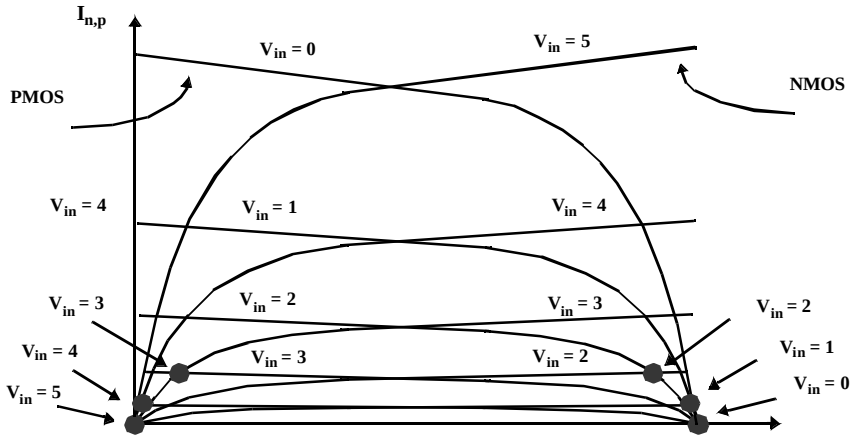
25 nm MOS transistor (Folded Channel)

Voltage Transfer Characteristic

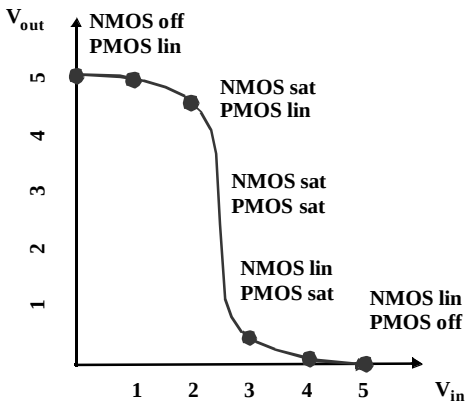
PMOS Load Lines



CMOS Inverter Load Characteristics



CMOS Inverter VTC



Simulated VTC